

IN THE CLAIMS:

1-26. (Canceled)

27. (Currently Amended) A method of manufacturing an electro-optical device comprising:

providing a substrate by a substrate holder in a film formation chamber;

forming a film comprising an organic material over the substrate by vapor deposition in the film formation chamber wherein said organic material is simultaneously deposited on said substrate holder;

removing said substrate from said ~~reaction~~ film formation chamber after forming said film;

irradiating a component said substrate holder provided in a ~~film forming~~ said film formation chamber with a light selected from the group consisting of infrared light, UV-light, and visible light, thereby sublimating a ~~vapor deposition material~~ said organic material adhering to the substrate holder component, after removing the substrate; and

exhausting the sublimated ~~vapor deposition material~~ organic material,

wherein the ~~vapor deposition material~~ organic material comprises an organic light emitting material.

28. (Currently Amended) A method of manufacturing a light emitting device comprising:

providing a substrate by a substrate holder in a film formation chamber;

forming a film comprising an organic material over the substrate by vapor deposition in the film formation chamber wherein said organic material is simultaneously deposited on said substrate holder;

removing said substrate from said ~~reaction~~ film formation chamber after forming said film;

irradiating a component said substrate holder provided in a ~~film forming~~ said film formation chamber with a light selected from the group consisting of infrared light, UV-light, and visible light, thereby sublimating a ~~vapor deposition material~~ said organic material adhering to the substrate holder component, after removing the substrate; and

exhausting the sublimated ~~vapor deposition material~~ organic material,
wherein the ~~vapor deposition material~~ organic material comprises an organic light
emitting material.

29. (Currently Amended) The method according to claim 27, wherein said light
selected from the group consisting of the infrared light, UV-light, and visible light is radiated
by using a light source provided in the ~~film-forming~~ film formation chamber.

30. (Original) The method according to claim 27, wherein an irradiation surface of
said light selected from the group consisting of the infrared light, UV-light, and visible light
is in a rectangular or oblong shape.

31. (Currently Amended) The method according to claim 27, further comprising a
step of supplying a halogen containing gas into the ~~film-forming~~ film formation chamber
during sublimating the ~~vapor deposition material~~ organic material.

32. (Original) The method according to claim 27, further comprising a step of
forming a plasma during exhausting.

33. (Original) The method according to claim 32, wherein said plasma is an
oxygen plasma.

34. (Currently Amended) The method according to claim 28, wherein said light
selected from the group consisting of the infrared light, UV-light, and visible light is radiated
by using a light source provided in the ~~film-forming~~ film formation chamber.

35. (Original) The method according to claim 28, wherein an irradiation surface of
said light selected from the group consisting of the infrared light, UV-light, and visible light
is in a rectangular or oblong shape.

36. (Currently Amended) The method according to claim 28, further comprising a step of supplying a halogen containing gas into the ~~film forming~~ film formation chamber during sublimating the ~~vapor deposition material~~ organic material.

37. (Original) The method according to claim 28, further comprising a step of forming a plasma during exhausting.

38. (Original) The method according to claim 37, wherein said plasma is an oxygen plasma.

39. (Currently Amended) A method of manufacturing a display device comprising:

providing a substrate by a substrate holder in a film formation chamber;

forming a film comprising an organic material over the substrate by vapor deposition in the film formation chamber wherein said organic material is simultaneously deposited on said substrate holder;

removing said substrate from said ~~reaction~~ film formation chamber after forming said film;

heating said organic material deposited on said substrate holder in said film formation chamber to vaporize said organic material, after removing the substrate;

exhausting the vaporized organic material from said film formation chamber.

40. (Original) The method according to claim 39, wherein said film comprising an organic material is a light emitting layer.

41. (Original) The method according to claim 39, further comprising a step of supplying a halogen containing gas into the film formation chamber during heating said organic material.

42. (Original) The method according to claim 39, further comprising exposing the vaporized organic material to a plasma.

43. (Currently Amended) A method of manufacturing a display device comprising:

providing a substrate by a substrate holder in a film formation chamber wherein an adhesion preventing shield is provided between said substrate and an inner wall of the film formation chamber;

forming a film comprising an organic material over the substrate by vapor deposition in the film formation chamber wherein said organic material is simultaneously deposited on said adhesion preventing shield;

removing said substrate from said reaction film formation chamber after forming said film;

heating said adhesion preventing shield to vaporize said organic material deposited on said adhesion preventing shield, after removing the substrate;

exhausting the vaporized organic material from said film formation chamber.

44. (Original) The method according to claim 43, wherein said film comprising an organic material is a light emitting layer.

45. (Original) The method according to claim 43, further comprising a step of supplying a halogen containing gas into the film formation chamber during heating said organic material.

46. (Original) The method according to claim 43, further comprising exposing the vaporized organic material to a plasma.

47. (Currently Amended) A method of manufacturing an electro-optical device comprising:

providing a substrate by a substrate holder in a film formation chamber;

forming a film comprising an organic material over the substrate by vapor deposition in the film formation chamber wherein said organic material is simultaneously deposited on said substrate holder;

removing said substrate from said reaction film formation chamber after forming said film;

irradiating a component substrate holder provided in a film forming said film formation chamber by scanning a lamp light source, thereby sublimating a vapor deposition material said organic material adhering to the component substrate holder, after removing the substrate; and

exhausting the sublimated vapor deposition material organic material,

wherein the vapor deposition material organic material comprises an organic light emitting material.

48. (Original) The method according to claim 47, wherein the lamp light source is selected from the group consisting of infrared light, UV-light, and visible light.

49. (Currently Amended) The method according to claim 47, further comprising a step of supplying a halogen containing gas into the film forming film formation chamber during sublimating the vapor deposition material organic material.

50. (Original) The method according to claim 47, further comprising a step of forming a plasma during exhausting.

51. (Original) The method according to claim 50, wherein said plasma is an oxygen plasma.

52. (New) A method of manufacturing a display device comprising:
forming a film comprising an organic material over a substrate by vapor deposition in a film formation chamber wherein said organic material is simultaneously deposited on equipments in the film formation chamber;

removing said substrate from said film formation chamber after forming said film;

irradiating said equipments provided in said film formation chamber with a light selected from the group consisting of infrared light, UV-light, and visible light, thereby

sublimating said organic material adhering to the equipments, after removing the substrate; and

exhausting the sublimated organic material,

wherein the organic material comprises an organic light emitting material.

53. (New) The method according to claim 52, wherein said equipments in the film formation chamber is a substrate holder, a mask holder, an adhesion preventing shield, or a vapor-deposition mask.

54. (New) The method according to claim 52, wherein said light selected from the group consisting of the infrared light, UV-light, and visible light is radiated by using a light source provided in the film formation chamber.

55. (New) The method according to claim 52, wherein an irradiation surface of said light selected from the group consisting of the infrared light, UV-light, and visible light is in a rectangular or oblong shape.

56. (New) The method according to claim 52, further comprising a step of supplying a halogen containing gas into the film formation chamber during sublimating the organic material.

57. (New) The method according to claim 52, further comprising a step of forming a plasma during exhausting.

58. (New) The method according to claim 52, wherein said plasma is an oxygen plasma.

59. (New) A method of manufacturing a display device comprising: forming a film comprising an organic material over a substrate by vapor deposition in a film formation chamber wherein said organic material is simultaneously deposited on equipments including in the film formation chamber;

removing said substrate from said film formation chamber after forming said film;
heating said organic material deposited on equipments provided in said film formation
chamber to vaporize said organic material, after removing the substrate;
exhausting the sublimated organic material.

60. (New) The method according to claim 59, wherein said equipments in the film
formation chamber is a substrate holder, a mask holder, an adhesion preventing shield, or a
vapor-deposition mask.

61. (New) The method according to claim 59, wherein said film comprising an
organic material is a light emitting layer.

62. (New) The method according to claim 59, further comprising a step of
supplying a halogen containing gas into the film formation chamber during heating said
organic material.

63. (New) The method according to claim 59, further comprising exposing the
vaporized organic material to a plasma.